## 반도체공정개론 Homework solutions

## Homework #1

1-a)

이 식 사용해서 설명한 경우 모두 정답 처리

1-b)

EUV의 photon energy가 높아서 렌즈에 투과가 아닌 흡수가 되어 열이 발생, 렌즈에 damage 발생되기 때문

1-c) 다음 4가지만 정답 처리

C) Double patterning.

② phase shift masks
③ optical - proximity correction techniques

② Double exposure

2-a)

0) 
$$A = area$$
  
 $V = Valume$   
 $\therefore SiO_{2}(g) = 2.21 \text{ Ax } (4)$   
 $SiO_{2}(mol) = \frac{2.21 \text{ Ax}}{60.08} (mol)$   
 $Si \text{ among } SiO_{2}(g)$   
 $= \frac{2.21 \text{ Ax}}{60.08} \times 28.9 (mol)$   
 $60.08$   
 $\therefore Si(ar^{2}) = \frac{2.21 \text{ Ax}}{60.02} \times \frac{28.9}{2.33}$   
 $= 0.456 \text{ Ax } \text{ ax}^{2}$   
 $A \in \text{ SiO}_{2} \text{ Fmi } 1 \text{ changes} \text{ and } \text{ ax}$   
 $\therefore SiO_{2} \text{ Fmi } 1 \text{ changes} \text{ ax}$ 

2-b) 0.7hr (그래프 보고 읽으면 됨, 이 외의 값은 오답)

## Homework #2

1-a)

0) Table 1 19 
$$D_0 = 10.5$$
 cm<sup>2</sup>6

 $E_X = 3.69$  eV

$$D = 105 \exp\left(-\frac{3.69}{(8.614 \times 10^{-13})(13.73)}\right)$$

$$= 2.96 \times 10^{-13} \text{ [cm2/5]}$$

1-b)

b) Table 1 10 
$$D = 10.5 \exp\left(-\frac{3.69}{10.5 (1423)}\right)$$
  
 $= 2.36 \times 10^{-13} \text{ cm}^{2}(5)$   
(Dt) tot =  $(2.96 \times 10^{-13} \text{ cm}^{2}/5) (12005)$   
 $= (.81 \times 10^{-8} \text{ [cm}^{-7}]$ 

1-c) (i)

C) i

Figure 2 
$$N$$
 boron = 1 solid - solubility limited surface concentration  $\sim 1.1 \times 10^{20}$  /cm<sup>3</sup>
 $N(x) = 1.1 \times 10^{20}$  erfc  $\left(\frac{2L}{2\sqrt{D_i t_i}}\right)$  been ortans/ $m^3$ 

Janction depth  $X_j \Rightarrow N(x) = N_B$  ( background concentration)

 $3 \times 10^{14}$  /cm<sup>3</sup>  $\sim F_{guine} 3$ 
 $\therefore 1.1 \times 10^{24}$  erfc  $\left(\frac{X_J}{2\sqrt{D_i t_i}}\right) = 3 \times 10^{14}$ 
 $N_j = 2\sqrt{D_i t_i}$  erfc<sup>-1</sup> (  $0.000213$ )

 $\sim F_{guine} 1$ 

= 2 \J 131 x 10 12 (2.51) cm

= 0,0587 um (58, 7 nm)

1-c) (ii)

C) ii  $Q = 2 \frac{1}{10} \sqrt{\frac{1}{10}} = 2 (1.1 \times 10^{2-}) \sqrt{\frac{100}{100}} / \pi$   $\therefore Q = 1.42 \times 10^{14} \text{ boron atoms/cm}^2$   $N(x) = \sqrt{\frac{2}{100}} \exp\left(-\frac{x_0}{200}\right)^2$   $= \sqrt{\frac{1}{100}} \exp\left(-\frac{x_0}{1.47 \times 10^{-4}}\right)^2$   $N_B = 3 \times 10^{16}$   $\sim \text{Figure 3}$   $\therefore 1.1 \times 10^{18} \exp\left(-\frac{x_0}{1.47 \times 10^{-4}}\right)^2 = 3 \times 10^{16}$ i)  $\approx \text{Nich} \approx \frac{22}{1000} \approx \frac{11 \times 10^{-4}}{1000} \times \frac{11 \times 10$ 

10 m = W-2 (30 cm) Cot (54,1) 10 m ~ W-J\_X (30 cm) W= 434. 26 mm

2)